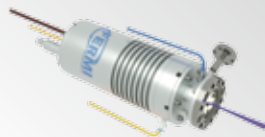
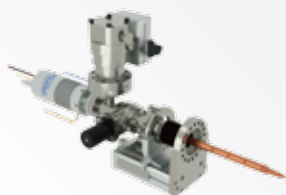


Section 7. VUV Source

BL1000S
(VUV Lamp Head)



BL1010S
(Xe/ Kr)



BL1100S
(He MONO)

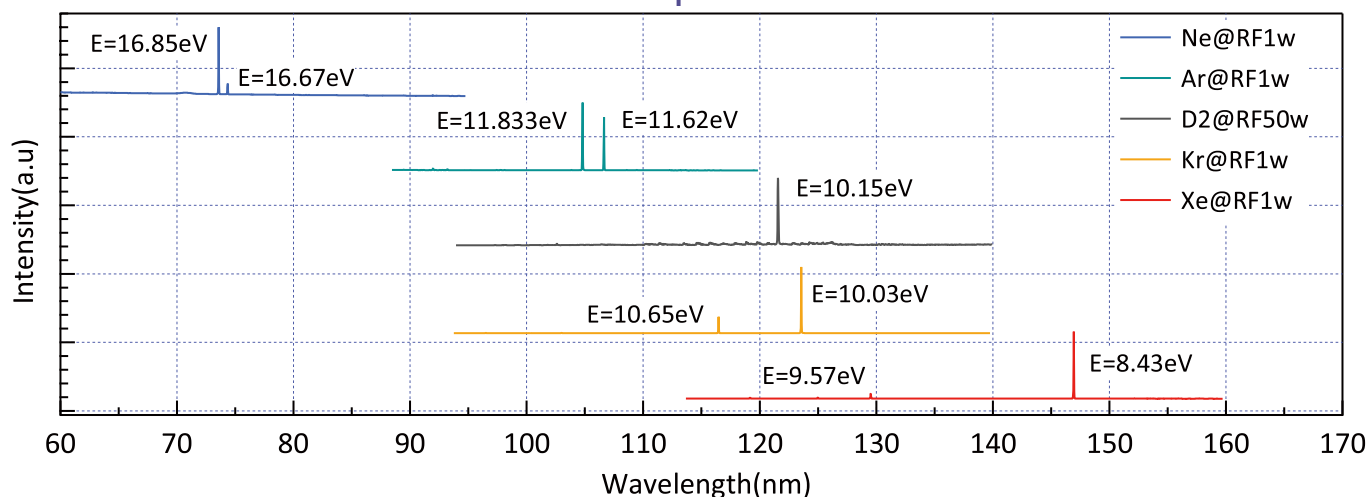


BL1200S
(Multi-gas MONO)



FERMI BL-1000 Series are ultra-high brilliance VUV Light Sources, based on the revolutionary RF Plasma mechanism, which can be operated with different gases (He, Ne, Ar, Kr, Xe...) and gas mixture. (Patent No.: 201610261838.5)

Broad Spectrum



Applications

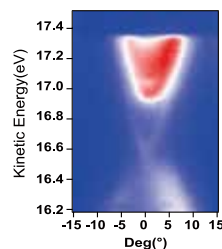
✓ UPS, ARPES, Mass Spectroscopy, etc.

Specification

- ✓ High Flux: $> 1 \times 10^{14}$ Photons / Sec
- ✓ Broad Sepctrum: 8.43eV-40.8eV(30nm-147nm)
- ✓ High Resolution: $< 1\text{meV}@8.43\text{eV}(\text{Xe})$
- ✓ Long Life Time: > 20000 hours
- ✓ Options: Focuse Optics (0.5mm spot size), Replaceable Filters(Xe@8.43eV, Kr@10.03eV), VUV MONO;

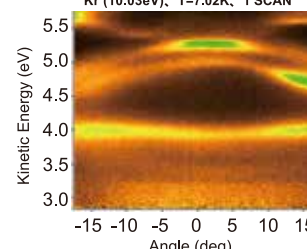
High Brilliance (VUV Flux $> 1 \times 10^{14}$ photons/sec)

He(21.2eV): $\text{Bi}_2\text{Se}_3@5.6\text{K}$



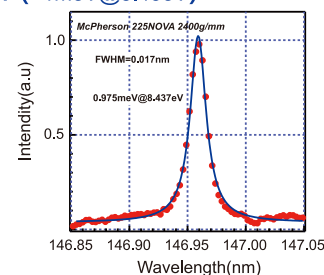
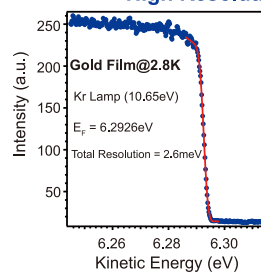
Courtesy of Prof. Y. H. Wang's system in Fudan University

Sample: NbGeSb single crystal
Kr (10.03eV), T=7.02K, 1 SCAN

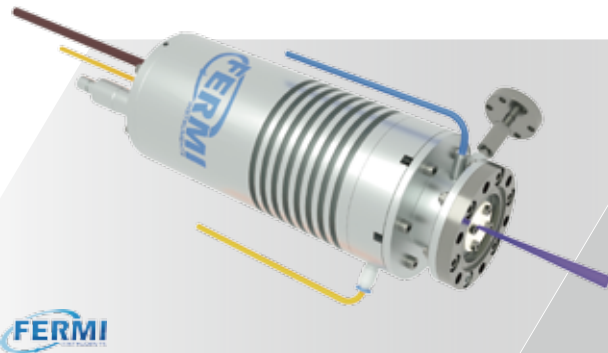


Courtesy of Prof. S. C. Wang's system in Renmin University

High Resolution ($< 1\text{meV}@8.43\text{eV}$)



Multi-Gas Ultra-High Flux VUV Source



The new FERMI BL-1000 is an ultra-high efficiency UV source based on revolutionary plasma local field mechanism, integrated with latest solid RF source technology. Providing orders of magnitude higher efficiency than traditional plasma-base UV sources.

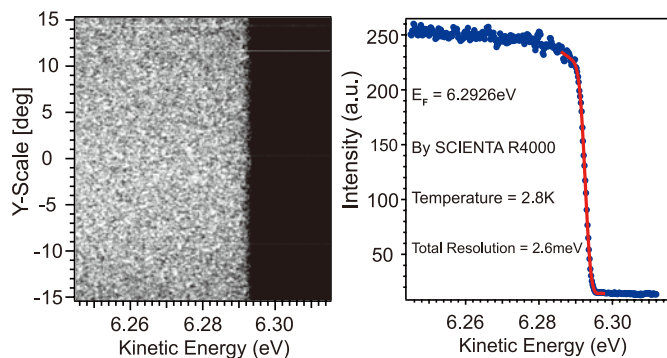
BL-1000 is an electrode-free and ignite-free universal UV source, which can work with various gases and gas mixture. Providing broad application, such as photoemission spectroscopy, mass spectroscopy, atomic absorption spectroscopy etc.

Specification

- ✓ Multiple Working Gases: He, Ne, Ar, Kr, Xe,...
- ✓ Photon Energy: 8.4eV-40.8eV(30nm-147nm)
- ✓ Photon Flux: $> 1 \times 10^{14}$ Photons/ Sec
with appropriate monochromator and capillary
- ✓ Resolution: $< 1\text{meV}@Xe$ (8.43eV)
- ✓ Compact solid RF source driven by 24V/200W power source
- ✓ UHV Compatible All Metal Seals

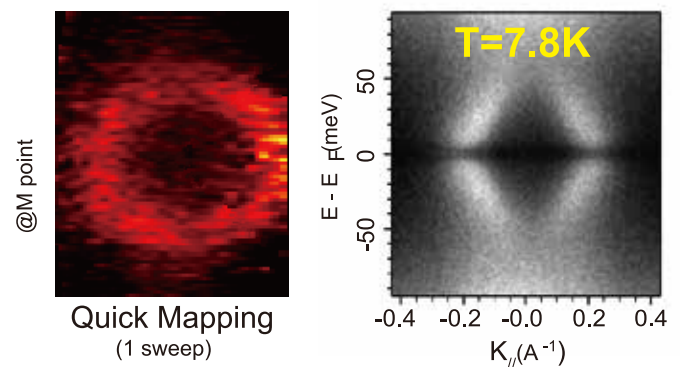


— Gold Thin Film —



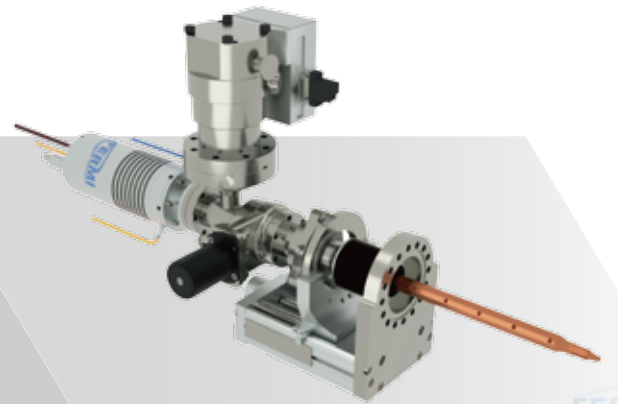
Courtesy of Prof. H. Ding's system in IOP, CAS

— FeSe Thin Film —



Courtesy of Prof. D.L. Feng's system in Fudan University

Focused VUV Source

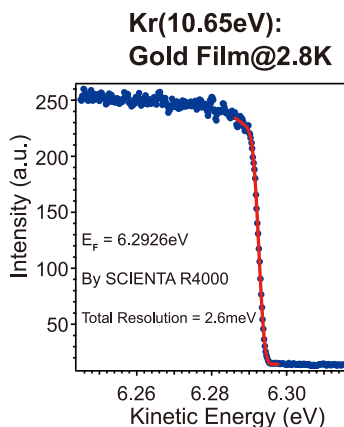


FIUV BL-1010s is a specially designed high brilliance multi-gas VUV Source with three-stage differential chamber and UHV valve isolated focusing capillary. It can be operated with a wide variety of different gases (He, Ar, Kr, Xe...) with small spot output and small working pressure increment.

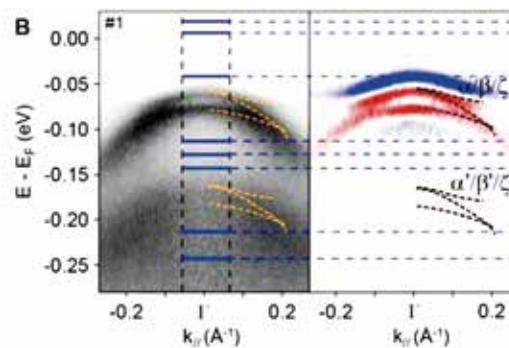
Specification

- ✓ Total VUV Flux: $>3 \times 10^{13}$ Photons/ Sec
- ✓ Photon Flux: $>1 \times 10^{12}$ Photons/ Sec on Sample
- ✓ Line Width: <1 meV @Xe(8.4eV)
- ✓ Three-Stage differential pumping
- ✓ High efficiency focus optics
- ✓ Retractable mechanism: 75mm Linear Translator
- ✓ Alignment Mechanism: Tilt mechanism: $\pm 3^\circ$
- ✓ Solid RF Power Supply
- ✓ Compulsory air cooling and water cooling
- ✓ All-metal-sealed, UHV compatible

Test Spetrum



Courtesy of Prof. H. Ding's system in IOP, CAS



Courtesy of Prof. D.L. Feng's system in Fudan University

**Spot size on sample
0.5mm-1mm**

